

Four-target Electron Beam Evaporator

In this system, different source metals one after the other can be deposited without breaking the vacuum. This system is dedicated for metallization of III-V semiconductor samples.

Specification:

- **Evacuation:** Diffusion pump backed by a rotary pump (250 lit/min) to achieve a vacuum of $1E-6$ Torr.
- **Digital Thickness Monitor:** Quartz crystal used to monitor the thickness of the deposited film and also to control the rate of evaporation with pneumatic source shutter. 8"

The following metals can be deposited:

- Gold-Germanium (88:12 by weight)
- Antimony
- Chromium
- Gadolinium
- Gold
- Indium
- Nickel
- Palladium
- Titanium
- Gold-Antimony
- Aluminum

